

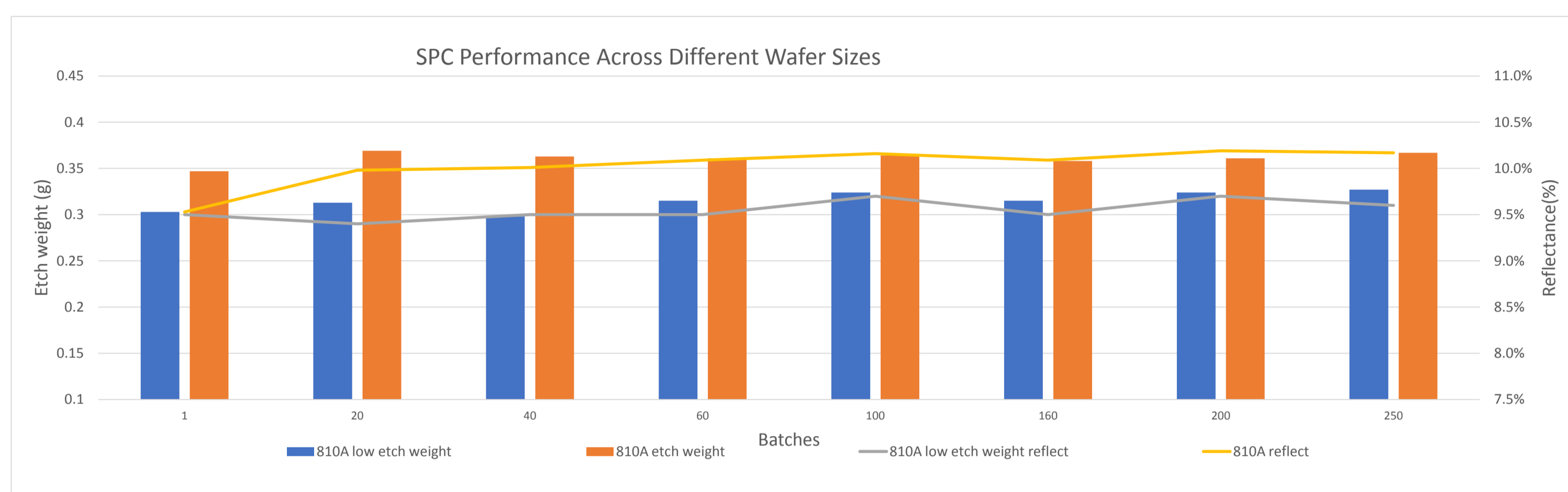
Mono-Si Texturization Additive MQT-810A

Increase Efficiency
SunFonergy's additive exhibits higher efficiency

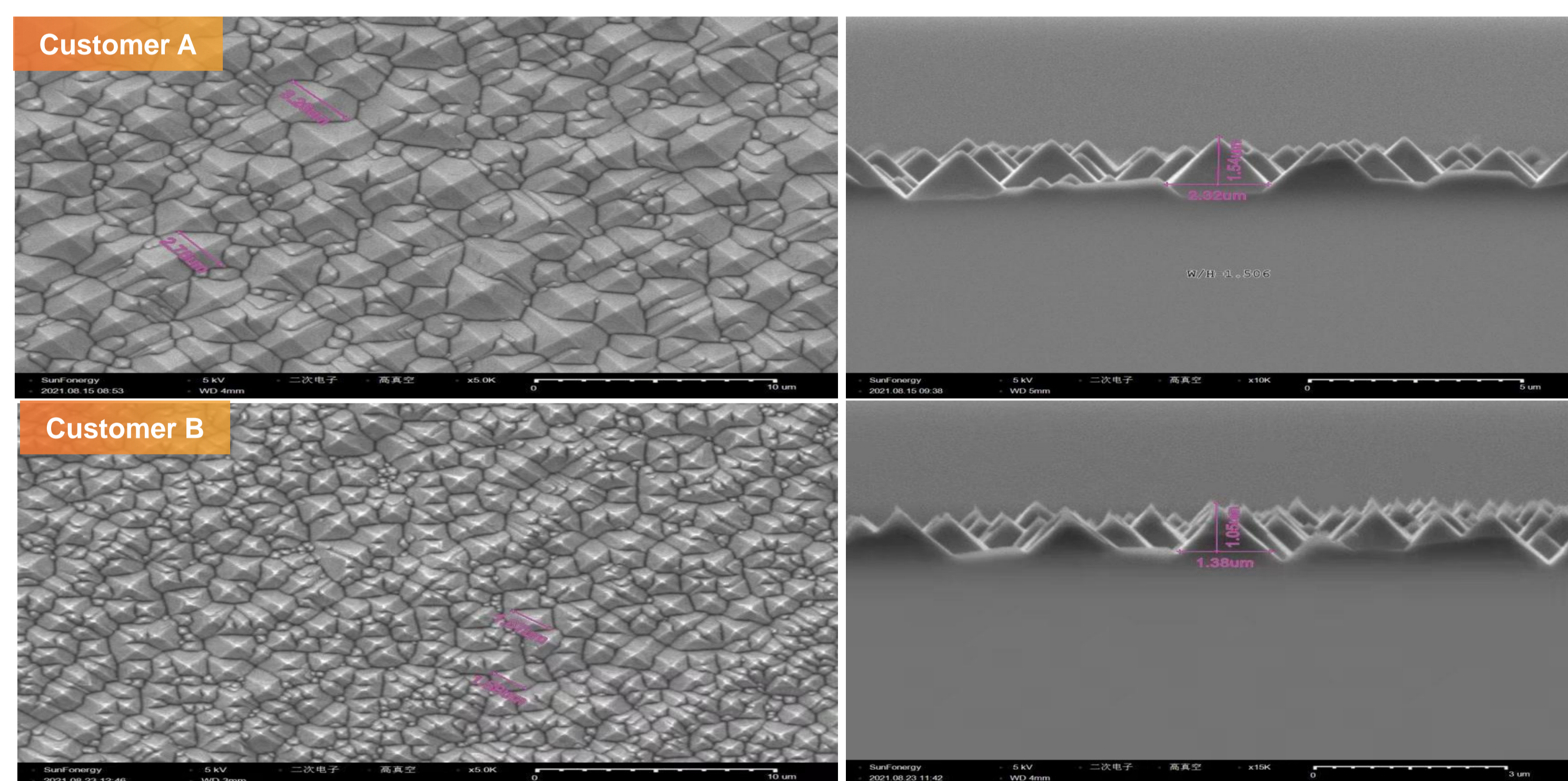


Item	Eta	Uoc	Isc	FF	IRev2	Rs	Rsh
Baseline	23.26	0.6888	13.656	81.617	0.060	0.0011	972.50
SunFonergy	23.29	0.6884	13.664	81.750	0.058	0.0010	871.40

Outstanding Stability
Low reflectance throughout bath lifetime with little variance, including for thin wafers



Better Morphology
Lower W/H ratio, with uniform morphology and wide window of pyramid size optimization



Cost Effective
SunFonergy's additive has a lower chemical consumption than that of competitors



Item	Initial Dosing (L)			Dosing (L / batch)		
	NaOH	DI	Additive	NaOH	DI	Additive
Baseline	6	490	2.2	0.45	16	0.14
SunFonergy	5.2	485	1.7	0.44	15	0.11

Increase Efficiency:
SunFonergy's additive exhibits higher efficiency

Outstanding Stability:
Low reflectance throughout bath lifetime with little variance, including for thin wafers

Uniform Morphology:
Denser morphology, wide window of pyramid size optimization

Cost Effective:
Lower chemical consumption